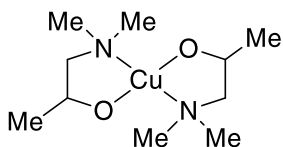


Catalog # 29-7120 Bis(dimethylamino-2-propxy)copper(II), min. 97% Cu(dmap)2



Thermal Behavior:

- Melting point: 139.4 [1]
- Decomposition: 185.4°C [1]
- TGA diagram and data is available in [1]
- Sublimation: 60-110°C/10⁻⁴ Torr [2], 70°C/10⁻³ Torr [3], 90°C/0.05 Torr [6]

Technical Notes:

1. ALD/CVD precursor for copper thin films and nanoparticle deposition.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Cu	ALD	70°C	0.3 Torr	Et ₂ Zn	80-200°C	4
	ALD	70°C	6-9 Torr	HCOOH, (H ₂ N) ₂	100-170°C	5
	ALD	100°C	6-9 Torr	BH ₃ (NHMe ₂)	110-175°C	6
	ALD	65°C	7.5 Torr	^t BuNHNH ₂	80-140°C	7
Cu ₂ O	ALD	100°C	-	H ₂ O	110-175°C	8
CuO	ALD	65°C	3.75 Torr	O ₃	80-140°C	9
	ALD	81-87°C	0.3 Torr	O ₃	140°C	10
CuO _x	ALD	100°C	0.1 Torr	O ₃ , H ₂ O	110-200°C	11
CuMn _x	ALD	-	-	Mn ₂ (^t BuNCHC(^t Bu)(Me)O) ₄ , BH ₃ (NHMe ₂)	160°C	12

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